

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Patent Application of

Michael Weber-Grabau, et al.

Application No.: 09/927,102

Filed: August 10, 2001

For: CRITICAL DIMENSION
METROLOGY SYSTEM
INTEGRATED INTO

SEMICONDUCTOR WAFER

PROCESS TOOL

Confirmation No.: 3815

Group Art Unit: 2877

Examiner: Richard A. Rosenberger

RESPONSE TO FINAL REJECTION MAILED JUNE 28, 2006

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M/S RCE Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450 CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail in an envelope, addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on September 27,2006.

STALLMAN & POLLOCK LLP

Dated: 09/7/2006

Bv:

Lana T. Brenner

Sir:

In response to the Office Action mailed June 28, 2006, and in conjunction with the Request for Continued Examination filed herewith, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the Listing of Claims that begins on page 2 of this paper.

Remarks begin on page 7 of this paper.

Atty Docket No.: TTI-31000